Measurement results of moving particles during STF cryomodule assembly under slow pumping/venting in KEK

<u>Hiroshi Sakai (KEK)</u>

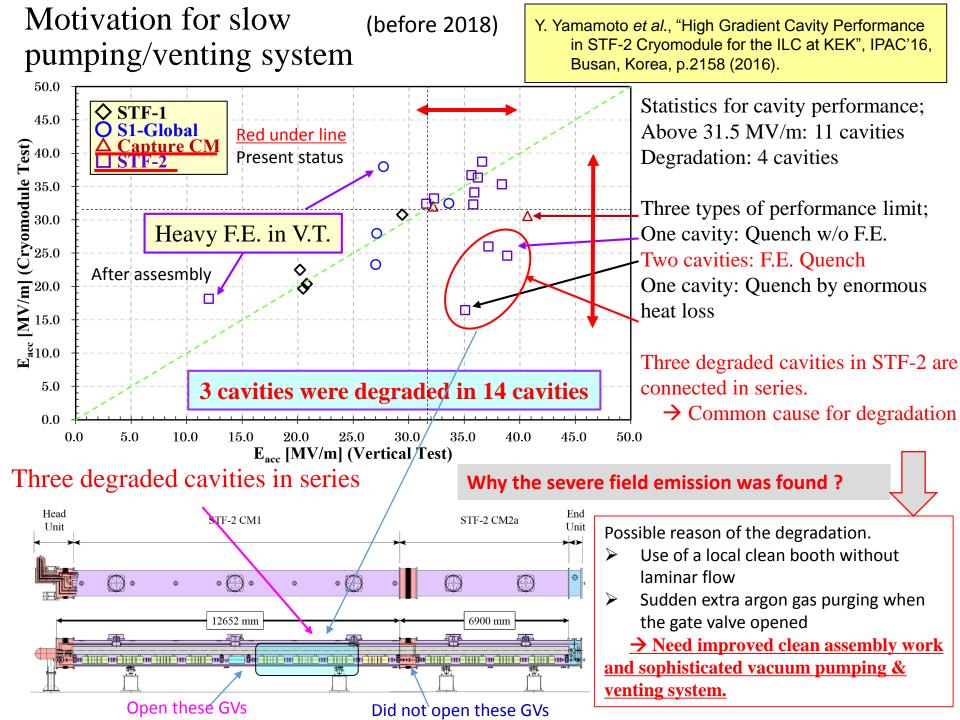
on behalf of SRF Grp.

STF cryomodule layout (For ILC Cryomodule test) STF-2 cryomodule 12 TFSLA like cavities STF Cavity Package

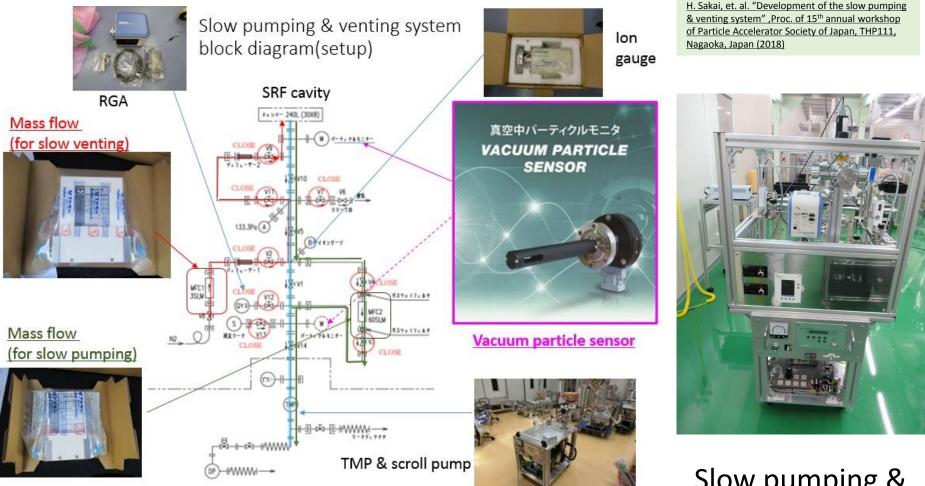


11 pages 1

TTC meeting @ CERN, 2020.Feb.6



slow pumping & venting system in KEK (First model 2018 @ KEK)



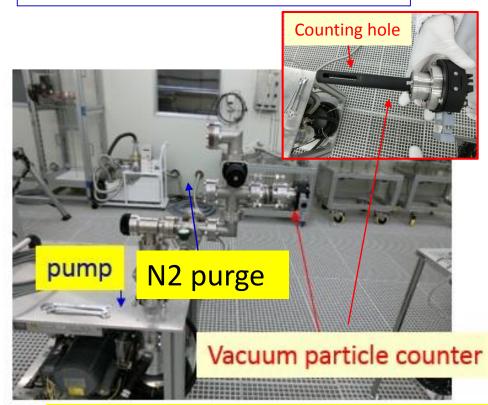
Slow pumping & venting system (parts) Light blue line is main pumping line. Green (red) line is slow pumping (venting) line.

Slow pumping & venting system (in KEK)

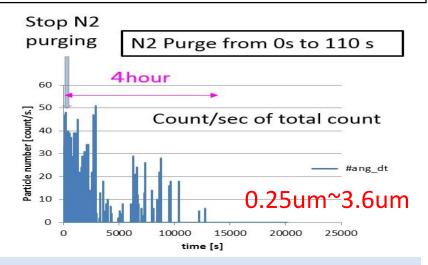
Test of vacuum particle sensor

Setup of vacuum particle sensor

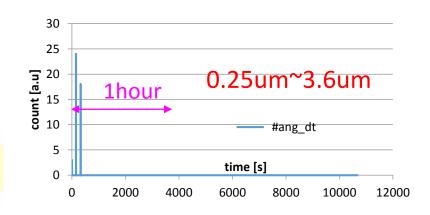
Particle measurement results after purging N2 with/without filter



We saw many particles after purging N2 gas w/o filter. Many particle come and stay in vacuum during 4 hours.

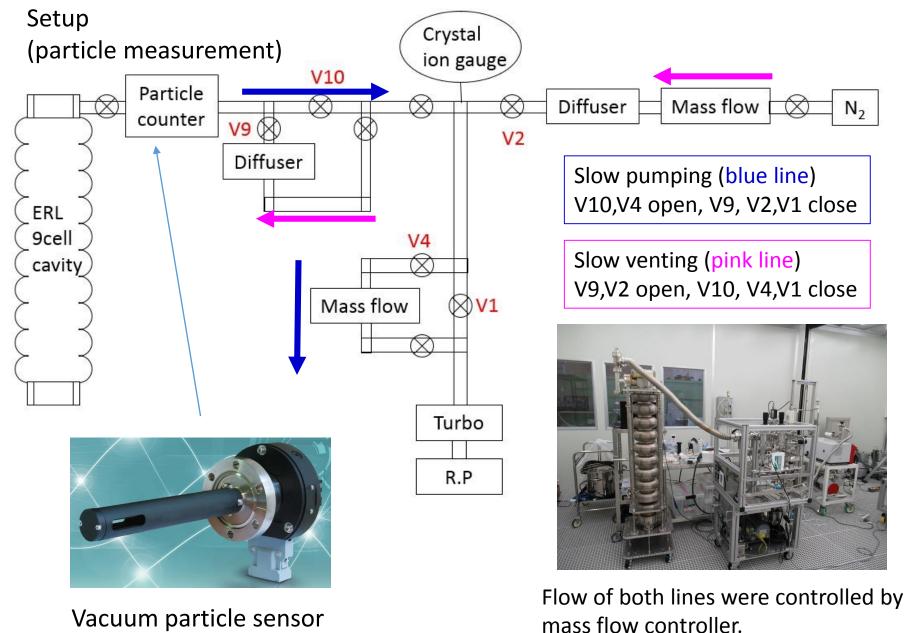


Particle was smaller than w/o filter case. Filter works to reduce particle contamination. But we saw the particle count during N2 purging both with and without filter of 5L/min flow



Venting is more dangerous than pumping. More slow pumping venting speed and optimization are needed to make slow pumping & venting system.

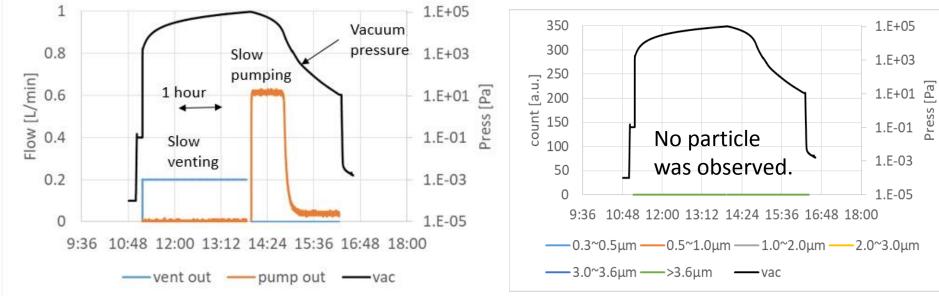
Test of slow pumping & venting system by using SRF cavity



Particle measurement results

Flow ratio and pressure under Slow pumping & venting

particle measurement results under slow pumping & venting as shown in left figure

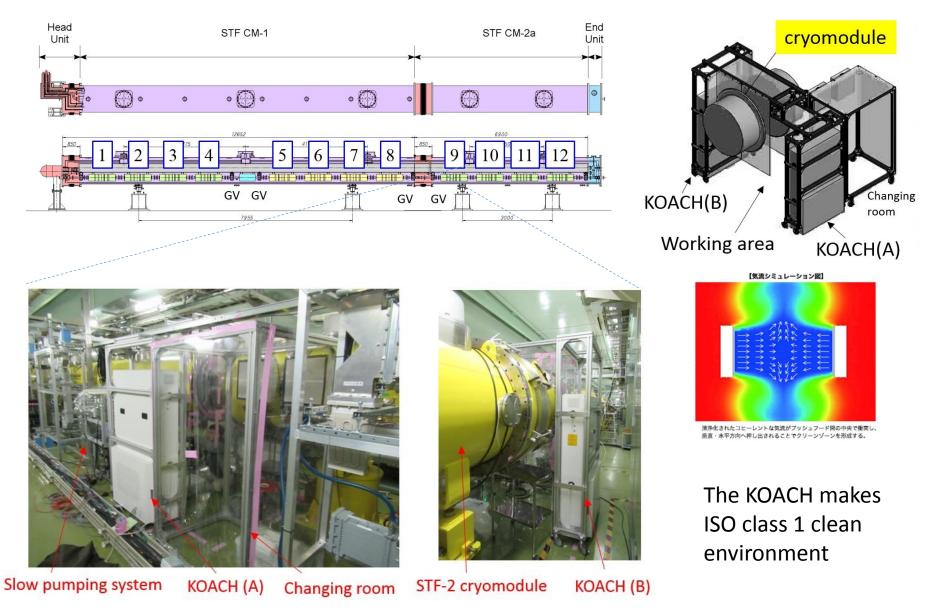


- <u>No particle of 0.3 um size was during slow</u> <u>pumping & venting of a few I/min speed.</u>
- <u>But during changing from the slow pumping to</u> <u>normal pumping by closing V1 valve. We found</u> <u>the particulate. Valve made particulate and</u> <u>need control closing/opening speed not to</u> <u>make particulate.</u>

speed	Gate Valve condition	Opening/closing time of vale	Particle number (0.3-0.5um)
slow	V1 open	1min 19sec	0
	V1 close	1min 4sec	0
normal	V1 open	14sec	0
	V1 close	12sec	0
fast	V1 open	5sec	32
	V1 close	6sec	6

Anyway, this slow pumping & venting system can apply our cryomodule in STF if optimize the valve control.

Setup for clean assembly between GVs



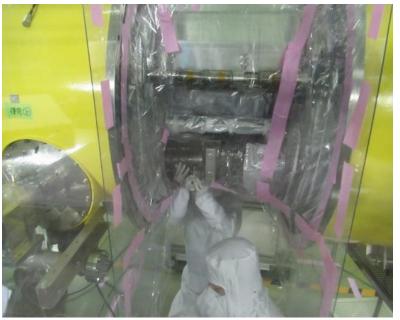
Layout of STF-2 cryomodule with the numbering of cavities.

7

<u>Reassembly work at new clean booth</u>



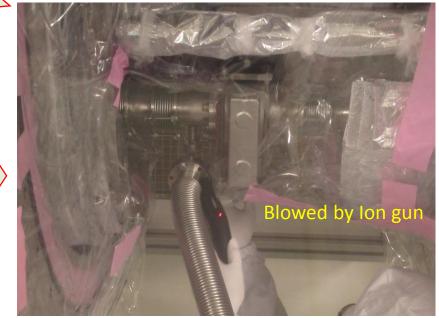
Remove the bellows between CM1 and CM2a in KOACH



Reconnect the bellows between CM1 and CM2a in KOACH



Wash the bellows by ultra-pure water and dried in class 10



pumped by new slow pumping & venting system

During slow pumping of bellows of STF cryomodule

Hit bellows under fastening bellows

140 1.00E+05 1.00E+04 120 1.00E+03 100 1.00E+02 Accumulated counts No increase under baking [Pa] 80 1.00E+01 0.5 1.00E+00 Ð 60 0.4 su 1.00E-01 0.3 Particle count 40 0.2 Pre 1.00E-02 20 1.00E-03 -0.1 12/10 1.00E-04 12/6 9:36 12/6 14:2412/6 19:12 12/7 0:00 12/7 4:48 12/7 9:36 - 3.0~3.6µm —>3.6µm Change Expanded view Expanded view Normal 1.00E+05 pumping 1.00E+05 140 1.00E+04 1.00E+03 TMP on 1.00E+04 1.00E+02 counts ulated counts 1.00E+01 [Pa] 1.00E+00 Accumulated 00E+03 1.005-01 1.00E-02 1.00E-03 1:00E+02 1.00E-04 17/6 14:31 12/6 15:00 12/6 15:14 -2.0~3.0un -3.0~3.6um ->3.6um 9 counts (0.3 μm - 0.5 μm) 55 counts (0.3 μm - 0.5 μm)

All pressure trend under pumping 1.00E+05

(close)

GV

ICF34

Slow

pumping

system

1.00E+04 1.00E+03

1.00E+02

1.00E+01

1.00E+00

1.000-01

1.00E-02 1.00E-03

1.00E-04

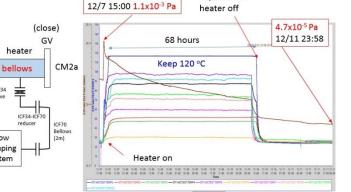
1.00E-05

CM1

Baking

trend

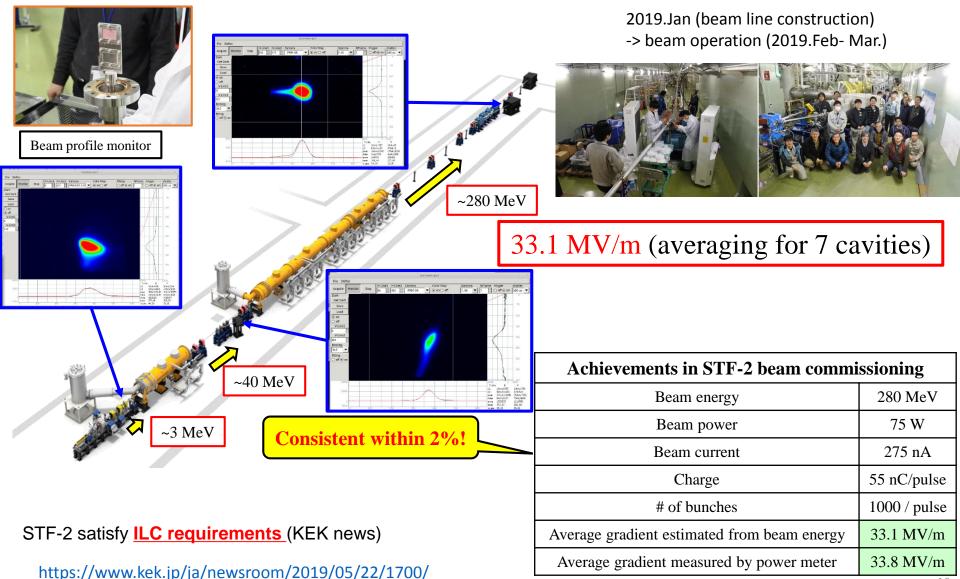
- After reaching 100 Pa, we changed the normal pumping by changing the GVs in slow pumping system.
- Totally, 125 counts with size between 0.3 µm and 0.5 μ m was found when we start slow pumping.
- TMP is one of the source of particulate.
- Valve was slowly open in more than 1 min.
- Finally, we opened the GVs between CM-1 and CM-2 after baking.



12/10 13:00

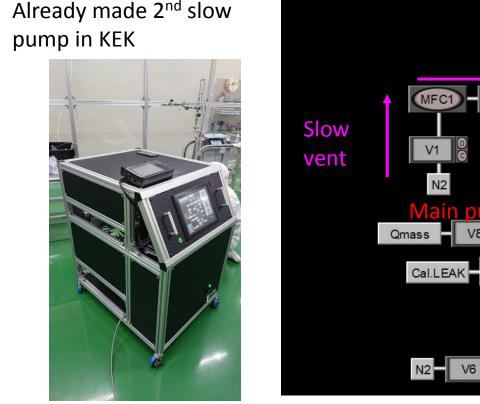
STF-2 high-G module study after clean assembly work (2019.Mar)

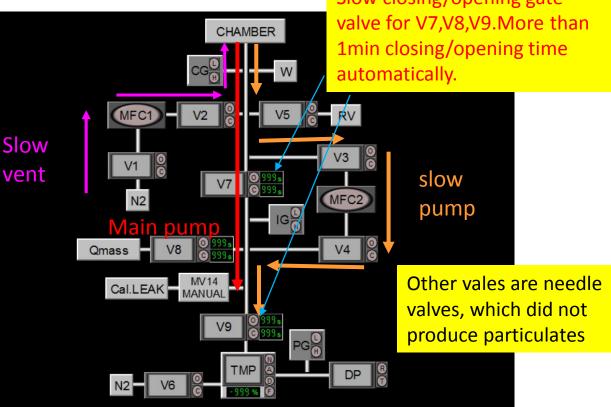
Courtesy of Y. Yamamoto



Summary & future plan

- Slow pumping & venting system works well. Slow closing/opening valve is important.
- This clean assembly work in new local clean booth and slow pumping/venting system with vacuum particle monitor helps keep clean environment of cryomodule assembly.
- Vacuum particle monitor give the important information duting slow pumping/venting
 Slow closing/opening gate



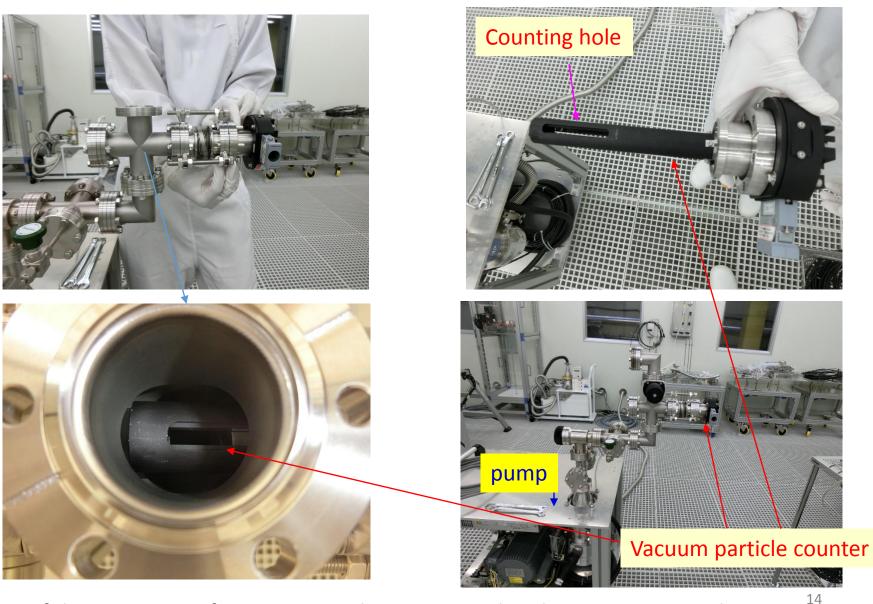


Acknowlegments

Yasuchika Yamamoto, Eiji Kako, Kensei Umemori, Taro Konomi, Takafumi Okada & All STF members Takashi Nogami & all cERL members Hiroki Yamada, Shinichi Imada, Asano, Tainaka, Ishihara of NAT Hirokazu Okada of K-vac Naomi Sasaki , Ichiro Mine of Fujikin company Kazuhiro Iimura of R-dec company, N. Sato of ELC company Hiroyuki Asada, Keiji Toriyama, Izumi Hattori of Wexx company

backup

All Shateld s except for monitor and gate valve are rinsed by high pressure water. All components are assembled in ISO class 4.



Position of the open area of vacuum particle counter in chamber

Final setup

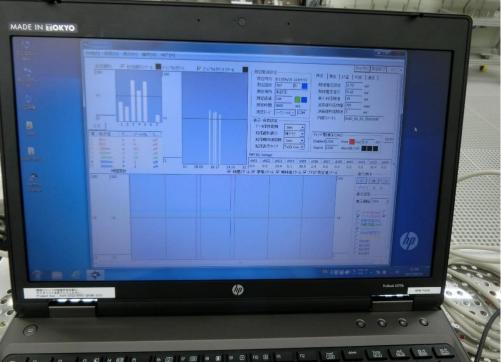
Particle counter & setup.

Browed by ion gun before setting.

Measurement setup in clean room



All PC and controller and cable was cleaned in clean room



Stop N[®]/leasurement of particle in N2 purge purging

N2 Purge from 0s to 110 s 4hour 60 50 Count/sec of total count 40 count [a.u.] 30 #ang_dt 20 10 0 5000 20000 0 10000 15000 25000 time [s] Integrated count in each particle size 1600 1400 1200 Integrated count Maximum : 1000 nx[2] 0.25um~0.6um range 800 nx[3] nx[4] 600 nx[5] 400 nx[6] 200 0 7 0 1 2 5 6 3 4 Time (hour)

We saw many particles after purging N2 gas w/o filter. Many particle come into and stay in vacuum during 4 hours.

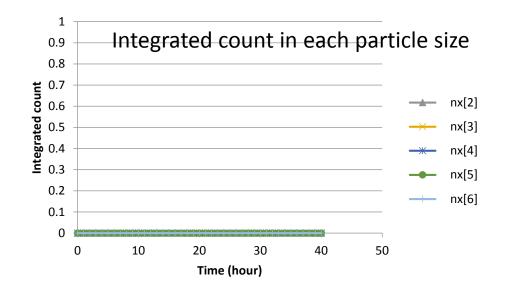
		number	Particle size
	_	namber	
		nx[2]	0.25um~0.6um
		nx[3]	0.6um~1.0um
		nx[4]	1.0um~3.0um
		nx[5]	3.0um~3.6um
		nx[6]	3.6um~



Particle

range

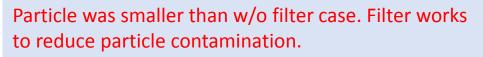
Pumping (not slow) after purging N2



	number	Particle size
Scroll ON	nx[2]	0.25um~0.6um
 start measurement 	nx[3]	0.6um~1.0um
•TMP on	nx[4]	1.0um~3.0um
	nx[5]	3.0um~3.6um
	nx[6]	3.6um~

We did not count by the vacuum particle counter when only we pump the vacuum.

Measurement of particle in N2 purge with filter 30 25 Count was observed. N2 flow: 5 L/min 20 But after 6min., count N2 stop after was stopped. 15 1min.



6000

time [s]

#ang dt

8000

10000

12000

count [a.u]

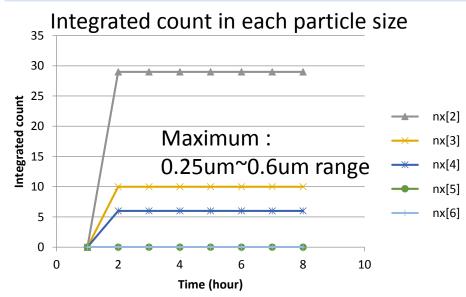
10

5

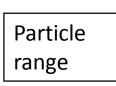
0 0

2000

4000



Anyway, we saw the particle count during N2 purging both with and without filter of 5L/min flow

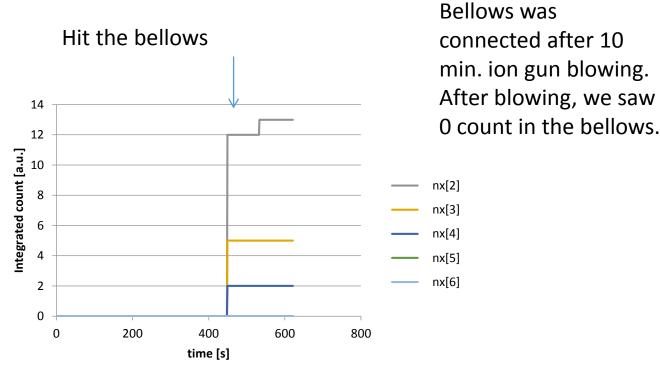


number	Particle size
nx[2]	0.25um~0.6um
nx[3]	0.6um~1.0um
nx[4]	1.0um~3.0um
nx[5]	3.0um~3.6um
nx[6]	3.6um~



Venting is more dangerous than pumping. More slow pumping speed and optimization are needed to make slow pumping system.

Hit the bellows after pumping



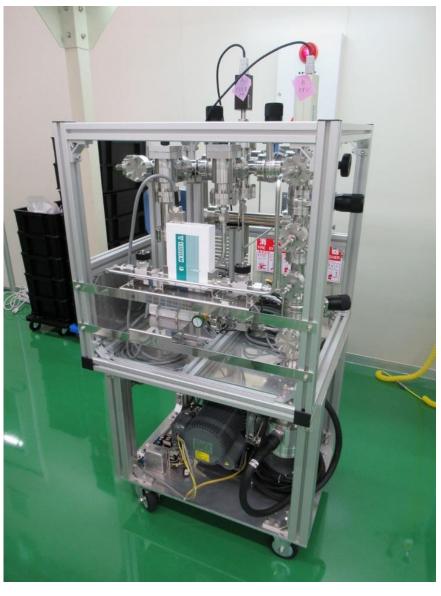
After hitting the bellows, we saw the particle count. Particle exists even though we blow inside the bellows by the ion gun.

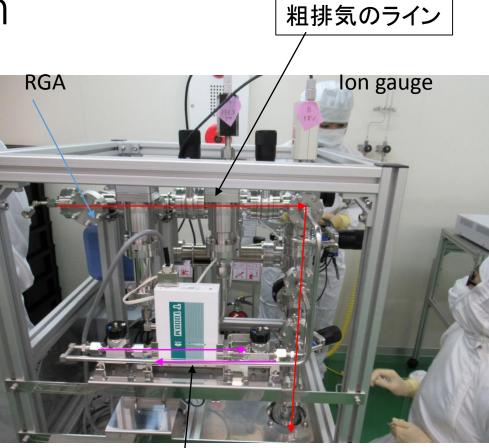
Particle range



	number	Particle size
-	nx[2]	0.25um~0.6um
	nx[3]	0.6um~1.0um
	nx[4]	1.0um~3.0um
	nx[5]	3.0um~3.6um
_	nx[6]	3.6um~

Slow pump system



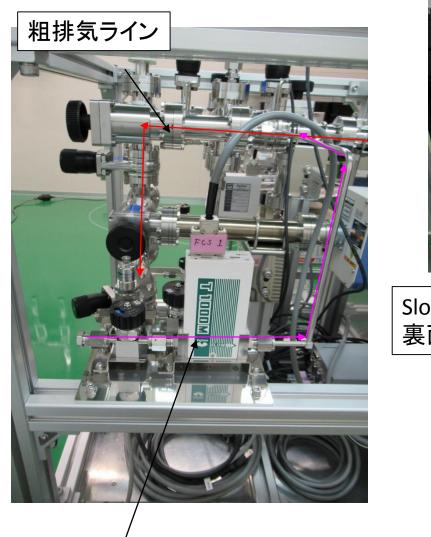


Massflowを入れたslowpumpのライン

高さ1.4m×横0.7m×縦0.7m



Slow pump system (2)



Mass flow+N2 slow purgeライン

